Highest resolution 3D printing in research and industry

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Nanoscribe's new Quantum X shape offers 3D Microfabrication capabilities with unmatched precision, based on Two-Photon Polymerization (2PP) and Nanoscribe's breakthrough technology of Two-Photon Grayscale Lithography (2GL ®) for surface patterning. It's superior precision relies on the highest voxel modulation rate in class, and an extremely fine address grid, allowing for sub-voxel size shape control. Making it the optimal tool for rapid prototyping and wafer-scale batch production of application designs in biomedical devices, microoptics, microelectromechanical systems (MEMS), microfluidics, surface engineering and many more [1].

References

[1] www.nanoscribe.com

Figures

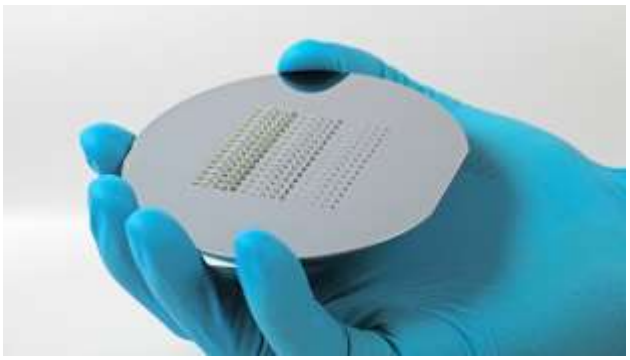

Figure 1: Batch processing of MEMS parts for batch processing on 4" wafer

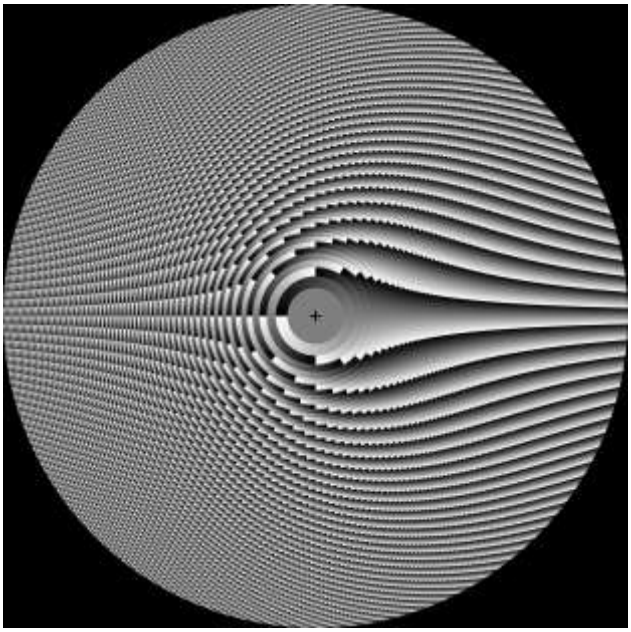

Figure 2: Diffractive Optical Element with pixel sizes down to 500 nm. Area: 2 mm x 2 mm (design Diffratec Optics OG)